

APPENDIX UNDER RULE 1.121

In the Abstract:

At page 20, please make the following changes to the Abstract as shown below:

[Abstract: The present invention relates to an apparatus and method for forming a plasma in the exhaust line of a primary process reactor. The plasma is generated in an inductive source (5) to examine the chemical concentrations of the waste or exhaust gas in vacuum lines that are below atmospheric pressure.

The optical radiation emitted by the plasma is analyzed by an optical spectrometer (9) and the resulting information is used to diagnose, monitor, or control operating states in the main vacuum vessel.]

The present invention includes devices and methods that form a plasma from process exhaust or other gas. More particularly, a plasma source is provided that is coupled to a spectrographic analyzer. Further aspects of the present invention are described in the specification and defined in the claims.